

**INFORMATION DISCLOSURE CITATION***(Use several sheets if necessary)*Docket number (Optional)
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Applicant(s)

Paz, et al.

Filing Date

01/25/2001

Group Art Unit

2141**U.S. PATENT DOCUMENTS**

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
<i>KLS</i>		5,838,927	11/17/1998	Gillon, et al.	395	200.77	11/22/1996
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<i>KLS</i>		6,208,354	03/27/2001	Porter	345	435	11/03/1998
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*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

FOREIGN PATENT DOCUMENTS

	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO

EXAMINER

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